

Supporting information

***Effect of Ho dopant on ferromagnetic characteristics of MoS₂
nanocrystals***

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From the EDS results (Table S1-S4), it can be concluded that the Ho doping concentration of the samples are 1.25, 1.54, 1.88 and 2.24 at.%.

Table S1. The composition of each elements of MoS₂:Ho³⁺ nanocrystals (1.25 at.%).

Element	Weight (%)	Atom (%)
S	38.77	66.04
Mo	57.46	32.71
Dy	3.77	1.25
Total	100	100

Table S2. The composition of each elements of MoS₂:Ho³⁺ nanocrystals (1.54 at.%).

Element	Weight (%)	Atom (%)
S	37.72	65.15
Mo	57.69	33.3
Dy	4.6	1.54
Total	100	100

Table S3. The composition of each elements of MoS₂:Ho³⁺ nanocrystals (1.88 at.%).

Element	Weight (%)	Atom (%)
S	39.44	66.98
Mo	54.86	31.14
Dy	5.7	1.88
Total	100	100

Table S4. The composition of each elements of MoS₂:Ho³⁺ nanocrystals (2.24 at.%).

Element	Weight (%)	Atom (%)
S	38.28	66.03
Mo	55.03	31.73
Dy	6.69	2.24
Total	100	100

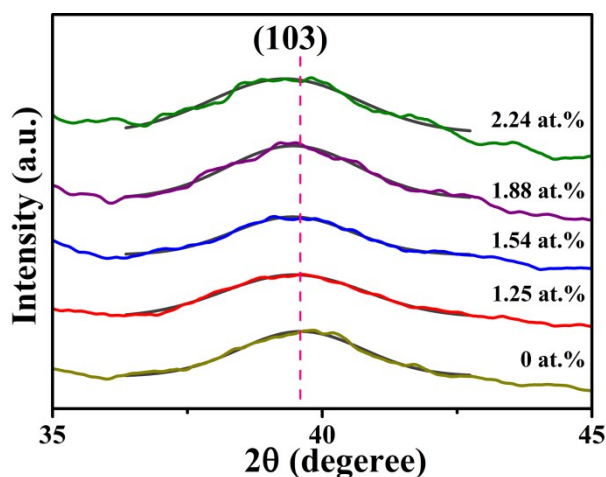


Figure S1 The variation of the (103) peak with Ho doping concentration obtained by Gaussian fitting.

Figure S2 shows the UV-Vis. Absorbance spectrum of pure and Ho-doped MoS₂ nanocrystals. The inset is plots of $(\alpha h\nu)^2$ vs $(h\nu)$ for the undoped and Ho-doped MoS₂ nanocrystals. From the pictures, it can be observed that the band gap values of are 2.19 eV, 2.27 eV, 2.32 eV, 2.34 eV and 2.37 eV for undoped, 1.25 at.%, 1.54 at.%, 1.88 at.% and 2.24 at.% MoS₂:Ho nanocrystals, which can be well in accordance with the reported results.¹ The increased band gap values as the increased Ho doping concentration indicate that the Ho ions are successfully incorporated into the MoS₂ host lattice.

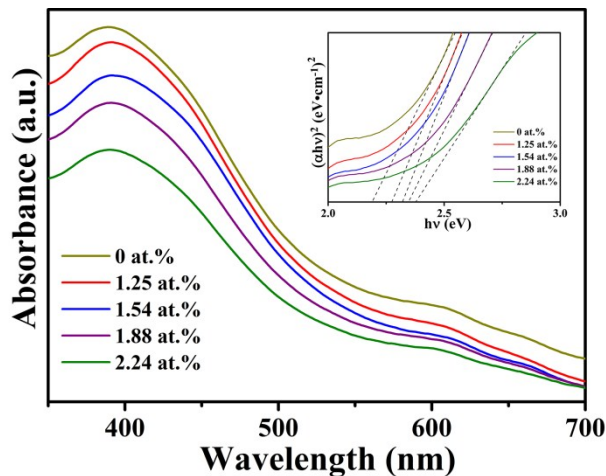


Figure S2 UV-Vis. absorbance spectrum of pure and Ho-doped MoS₂ nanocrystals. The inset is Plots of $(\alpha h\nu)^2$ vs $(h\nu)$ for the undoped and Ho-doped MoS₂ nanocrystals.

The PL spectra of the undoped MoS₂ nanocrystals and Ho-doped MoS₂ nanocrystals are shown in Figure S3. It can be observed a broad emission peak located at 650 nm which is similar to the reported results.^{2, 3} The PL spectrum of 1.54 at.% MoS₂:Ho shows the weak emission peak at 630 nm which is associated with excitonic transition^{3, 4}.

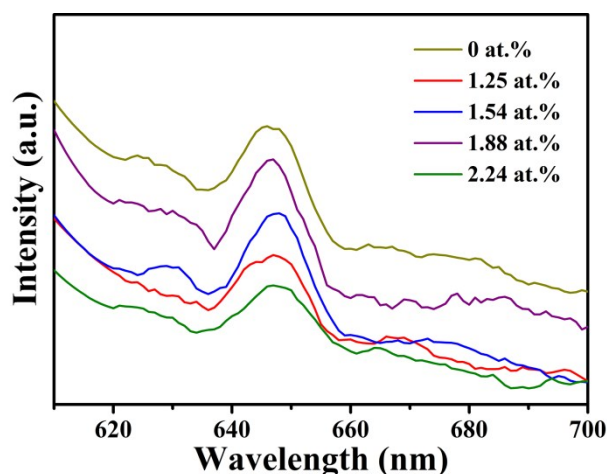


Figure S3 PL spectra of the undoped MoS₂ nanocrystals and the Ho-doped MoS₂ nanocrystals upon excitation by 475 nm at room-temperature.

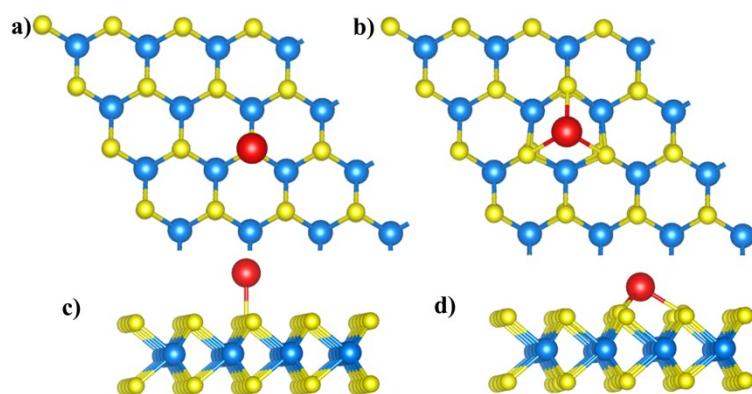


Figure S4 The atomic structures of $4 \times 4 \times 1$ MoS₂ supercells from top view of a) S-top (a Ho atom above the top of S atom) and b) HC (a Ho atom above the center of the S-Mo-S hexagonal ring). c) and d) The side view of the two structures.

In this work, a 4×4 doping slab model was built to study the magnetic properties of the Ho-doped MoS₂, including 48 atoms (32 S atoms, 15 Mo atoms and 1 Ho atom). The 15 Mo atoms contain 6 nearest neighboring Mo₁ atoms, 5 the next nearest neighboring Mo₂ atoms and 4 Mo atoms on other positions. Based on the new results, the magnetic moments of Mo₁ atoms are 0.976 μ B, 0.968 μ B, 0.964 μ B, 0.966 μ B, 0.966 μ B and 0.975 μ B. The magnetic moments of Mo₂ atoms are -1.823 μ B, 0.566 μ B, 0.554 μ B, -1.824 μ B and -1.823 μ B. The magnetic moments of Mo atoms on other positions are 1.09 μ B, 1.092 μ B, 1.092 μ B and 0.551 μ B. The overall magnetic moment of all the Mo atoms is 4.848 μ B. The overall magnetic moment of all the S atoms is -1.103 μ B. The magnetic moment of Ho atom is -2.348 μ B. Hence, the overall magnetic moment is 1.839 μ B.

References

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